# Andre Anders

List of Publications by Year
in descending order

Source: https://exaly.com/author-pdf/4939662/publications.pdf

Version: 2024-02-01

| | | | |
|---|---|---|---|
| 415 papers | 16,305 citations | 16411 64 h-index | 24179 110 g-index |
| 427 all docs | 427 docs citations | 427 times ranked | 7777 citing authors |

| # | Article | IF | Citations |
|---|---|---|---|
| 1 | Influence of the magnetic field on the discharge physics of a high power impulse magnetron sputtering discharge. Journal Physics D: Applied Physics, 2022, 55, 015202. | 1.3 | 20 |
| 2 | On the population density of the argon excited levels in a high power impulse magnetron sputtering discharge. Physics of Plasmas, 2022, 29, 023506. | 0.7 | 1 |
| 3 | High-quality transparent conductive indium oxide film deposition by reactive pulsed magnetron sputtering: Determining the limits of substrate heating. Applied Surface Science, 2022, 585, 152604. | 3.1 | 6 |
| 4 | 10.1063/5.0088430.1. , 2022, , . | | 0 |
| 5 | Building on excellence and reputation, a more inclusive Journal of Applied Physics evolves. Journal of Applied Physics, 2022, 131, . | 1.1 | 0 |
| 6 | Dynamics and 2D temperature distribution of plasma obtained by femtosecond laser-induced breakdown. Journal Physics D: Applied Physics, 2022, 55, 125204. | 1.3 | 4 |
| 7 | Properties of gallium oxide thin films grown by ion beam sputter deposition at room temperature. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, . | 0.9 | 2 |
| 8 | Foundations of physical vapor deposition with plasma assistance. Plasma Sources Science and Technology, 2022, 31, 083001. | 1.3 | 27 |
| 9 | Meeting todayâ€™s needs in applied physics publishing. Journal of Applied Physics, 2021, 129, . | 1.1 | 1 |
| 10 | On the electron energy distribution function in the high power impulse magnetron sputtering discharge. Plasma Sources Science and Technology, 2021, 30, 045011. | 1.3 | 15 |
| 11 | Role of Reaction Intermediate Diffusion on the Performance of Platinum Electrodes in Solid Acid Fuel Cells. Catalysts, 2021, 11, 1065. | 1.6 | 3 |
| 12 | Unravelling the ion-energy-dependent structure evolution and its implications for the elastic properties of (V,Al)N thin films. Acta Materialia, 2021, 214, 117003. | 3.8 | 20 |
| 13 | Cathode spot behavior in nitrogen and oxygen gaseous atmospheres and concomitant cathode surface modifications. Surface and Coatings Technology, 2021, 421, 127441. | 2.2 | 8 |
| 14 | High-resolution observation of cathode spots in a magnetically steered vacuum arc plasma source. Plasma Sources Science and Technology, 2021, 30, 095005. | 1.3 | 10 |
| 15 | Properties of secondary ions in ion beam sputtering of Ga2O3. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, . | 0.9 | 4 |
| 16 | On how to measure the probabilities of target atom ionization and target ion back-attraction in high-power impulse magnetron sputtering. Journal of Applied Physics, 2021, 129, . | 1.1 | 17 |
| 17 | Streak image observations of vacuum arc spots in a magnetically steered arc plasma source. , 2021, , . | | 0 |
| 18 | High-resolution observation of cathodic arc spots in a magnetically steered arc plasma source in low pressure argon, nitrogen, and oxygen atmospheres. Journal of Applied Physics, 2021, 130, . | 1.1 | 5 |

| # | Article | IF | Citations |
|---|---|---|---|
| 19 | Electron transport in high power impulse magnetron sputtering at low and high working gas pressure. Journal of Applied Physics, 2021, 130, . | 1.1 | 4 |
| 20 | Physics of high power impulse magnetron sputtering discharges. , 2020, , 265-332. | | 8 |
| 21 | Erosion and cathodic arc plasma of Nbâ€“Al cathodes: composite versus intermetallic. Plasma Sources Science and Technology, 2020, 29, 025022. | 1.3 | 10 |
| 22 | Vanadium oxide coatings to self-regulate current sharing in high-temperature superconducting cables and magnets. Journal of Applied Physics, 2020, 128, . | 1.1 | 8 |
| 23 | Insights into surface modification and erosion of multi-element arc cathodes using a novel multilayer cathode design. Journal of Applied Physics, 2020, 127, . | 1.1 | 13 |
| 24 | Optimizing the deposition rate and ionized flux fraction by tuning the pulse length in high power impulse magnetron sputtering. Plasma Sources Science and Technology, 2020, 29, 05LT01. | 1.3 | 46 |
| 25 | Serving a scientific community in an evolving research landscape. Journal of Applied Physics, 2020, 127, . | 1.1 | 1 |
| 26 | Properties of secondary particles for ion beam sputtering of silicon using low-energy oxygen ions. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, 033011. | 0.9 | 6 |
| 27 | Ion beam sputtering of silicon: Energy distributions of sputtered and scattered ions. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, . | 0.9 | 15 |
| 28 | Micro-propulsion based on vacuum arcs. Journal of Applied Physics, 2019, 125, . | 1.1 | 38 |
| 29 | Influence of Ar gas pressure on ion energy and charge state distributions in pulsed cathodic arc plasmas from Nbâ€“Al cathodes studied with high time resolution. Journal Physics D: Applied Physics, 2019, 52, 055201. | 1.3 | 5 |
| 30 | Plasma studies of a linear magnetron operating in the range from DC to HiPIMS. Journal of Applied Physics, 2018, 123, 043302. | 1.1 | 21 |
| 31 | Reduced atomic shadowing in HiPIMS: Role of the thermalized metal ions. Applied Surface Science, 2018, 433, 934-944. | 3.1 | 27 |
| 32 | Time and Energy-resolved Average Ion Charge States in Pulsed Cathodic Vacuum Arc Plasmas of Nb-A1 Cathodes as a Function of Ar Pressure. , 2018, , . | | 0 |
| 33 | Time-resolved ion energy and charge state distributions in pulsed cathodic arc plasmas of Nbâˆ’Al cathodes in high vacuum. Plasma Sources Science and Technology, 2018, 27, 055007. | 1.3 | 10 |
| 34 | Structural and Optical Studies of InGaN/GaN Superlattices Implanted with Eu Ions. MRS Advances, 2017, 2, 179-187. | 0.5 | 0 |
| 35 | Plasma potential of a moving ionization zone in DC magnetron sputtering. Journal of Applied Physics, 2017, 121, . | 1.1 | 69 |
| 36 | Sputtering of pure boron using a magnetron without a radio-frequency supply. Review of Scientific Instruments, 2017, 88, 043506. | 0.6 | 16 |

| # | Article | IF | Citations |
|---|---|---|---|
| 37 | Tutorial: Reactive high power impulse magnetron sputtering (R-HiPIMS). Journal of Applied Physics, 2017, 121, . | 1.1 | 275 |
| 38 | Direct observation of spoke evolution in magnetron sputtering. Applied Physics Letters, 2017, 111, . | 1.5 | 24 |
| 39 | Phase tailoring of tantalum thin films deposited in deep oscillation magnetron sputtering mode. Surface and Coatings Technology, 2017, 314, 97-104. | 2.2 | 27 |
| 40 | All-solid-state tunable Bragg filters based on a phase transition material. , 2017, , . | | 0 |
| 41 | Tunable Bragg filters with a phase transition material defect layer. Optics Express, 2016, 24, 20365. | 1.7 | 19 |
| 42 | Evidence for breathing modes in direct current, pulsed, and high power impulse magnetron sputtering plasmas. Applied Physics Letters, 2016, 108, . | 1.5 | 21 |
| 43 | Micropropulsion Based on Vacuum Arc Physics and Technology: A Review. , 2016, , . | | 2 |
| 44 | Editorial: Celebrating the 85th Anniversary of Journal of Applied Physics. Journal of Applied Physics, 2016, 119, 010401. | 1.1 | 0 |
| 45 | Influence of ionisation zone motion in high power impulse magnetron sputtering on angular ion flux and NbO<sub>x</sub>film growth. Plasma Sources Science and Technology, 2016, 25, 015022. | 1.3 | 28 |
| 46 | Temporal evolution of ion energy distribution functions and ion charge states of Cr and Cr-Al pulsed arc plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2015, 33, 061301. | 0.9 | 6 |
| 47 | Room Temperature Oxide Deposition Approach to Fully Transparent, Allâ€Oxide Thinâ€Film Transistors. Advanced Materials, 2015, 27, 6090-6095. | 11.1 | 57 |
| 48 | Editorial: Raising the barâ€"Providing a home. Journal of Applied Physics, 2015, 117, 010401. | 1.1 | 1 |
| 49 | Element- and charge-state-resolved ion energies in the cathodic arc plasma from composite AlCr cathodes in argon, nitrogen and oxygen atmospheres. Surface and Coatings Technology, 2015, 272, 309-321. | 2.2 | 18 |
| 50 | Adding high time resolution to charge-state-specific ion energy measurements for pulsed copper vacuum arc plasmas. Plasma Sources Science and Technology, 2015, 24, 045010. | 1.3 | 15 |
| 51 | Plasma of Vacuum Discharges: The Pursuit of Elevating Metal Ion Charge States, Including a Recent Record of Producing Bi<sup>13+</sup>. IEEE Transactions on Plasma Science, 2015, 43, 2310-2317. | 0.6 | 16 |
| 52 | Ion energies in high power impulse magnetron sputtering with and without localized ionization zones. Applied Physics Letters, 2015, 106, . | 1.5 | 25 |
| 53 | Localized heating of electrons in ionization zones: Going beyond the Penning-Thornton paradigm in magnetron sputtering. Applied Physics Letters, 2014, 105, 244104. | 1.5 | 51 |
| 54 | Propagation direction reversal of ionization zones in the transition between high and low current magnetron sputtering. Applied Physics Letters, 2014, 105, . | 1.5 | 36 |

| # | Article | IF | Citations |
|---|---|---|---|
| 55 | Controlling ion fluxes during reactive sputter-deposition of SnO2:F. Journal of Applied Physics, 2014, 116, . | 1.1 | 18 |
| 56 | Editorial: Journal of Applied Physics in a changing world of scientific publication. Journal of Applied Physics, 2014, 116, 010401. | 1.1 | 0 |
| 57 | Fermi level stabilization and band edge energies in CdxZn1â^'xO alloys. Journal of Applied Physics, 2014, 115, . | 1.1 | 37 |
| 58 | Dyke Award - Ffor distinguished work on discharges and electrical insulation in vacuum. , 2014, , . | | 0 |
| 59 | Ion energies in vacuum arcs: A critical review of data and theories leading to traveling potential humps. , 2014, , . | | 4 |
| 60 | 2-D mathematical modeling for a large electrochromic windowâ€"Part I. Solar Energy Materials and Solar Cells, 2014, 120, 1-8. | 3.0 | 21 |
| 61 | Smoothing of Discharge Inhomogeneities at High Currents in Gasless High Power Impulse Magnetron Sputtering. IEEE Transactions on Plasma Science, 2014, 42, 2856-2857. | 0.6 | 10 |
| 62 | Drifting Ionization Zone in DC Magnetron Sputtering Discharges at Very Low Currents. IEEE Transactions on Plasma Science, 2014, 42, 2578-2579. | 0.6 | 19 |
| 63 | Unusual Cathode Erosion Patterns Observed for Steered Arc Sources. IEEE Transactions on Plasma Science, 2014, 42, 2602-2603. | 0.6 | 4 |
| 64 | Asymmetric particle fluxes from drifting ionization zones in sputtering magnetrons. Plasma Sources Science and Technology, 2014, 23, 025007. | 1.3 | 49 |
| 65 | On the road to self-sputtering in high power impulse magnetron sputtering: particle balance and discharge characteristics. Plasma Sources Science and Technology, 2014, 23, 025017. | 1.3 | 55 |
| 66 | A review comparing cathodic arcs and high power impulse magnetron sputtering (HiPIMS). Surface and Coatings Technology, 2014, 257, 308-325. | 2.2 | 200 |
| 67 | Observation of multiple charge states and high ion energies in high-power impulse magnetron sputtering (HiPIMS) and burst HiPIMS using a LaB<sub>6</sub>target. Plasma Sources Science and Technology, 2014, 23, 035001. | 1.3 | 22 |
| 68 | Spectroscopic imaging of self-organization in high power impulse magnetron sputtering plasmas. Applied Physics Letters, 2013, 103, . | 1.5 | 51 |
| 69 | On sheath energization and Ohmic heating in sputtering magnetrons. Plasma Sources Science and Technology, 2013, 22, 045005. | 1.3 | 72 |
| 70 | Size and composition-controlled fabrication of thermochromic metal oxide nanocrystals. Journal Physics D: Applied Physics, 2013, 46, 362001. | 1.3 | 18 |
| 71 | Drifting potential humps in ionization zones: The â€œpropeller bladesâ€•of high power impulse magnetron sputtering. Applied Physics Letters, 2013, 103, . | 1.5 | 75 |
| 72 | Transparent and conductive indium doped cadmium oxide thin films prepared by pulsed filtered cathodic arc deposition. Applied Surface Science, 2013, 265, 738-744. | 3.1 | 55 |

| # | Article | IF | Citations |
|---|---|---|---|
| 73 | Structural, optical, and electrical properties of indium-doped cadmium oxide films prepared by pulsed filtered cathodic arc deposition. Journal of Materials Science, 2013, 48, 3789-3797. | 1.7 | 28 |
| 74 | Dopant-induced band filling and bandgap renormalization in CdOâ€‰:â€‰In films. Journal Physics D: Applied Physics, 2013, 46, 195102. | 1.3 | 35 |
| 75 | Estimating electron drift velocities in magnetron discharges. Vacuum, 2013, 89, 53-56. | 1.6 | 18 |
| 76 | Crystal structure and properties of CdxZn1âˆ’xO alloys across the full composition range. Applied Physics Letters, 2013, 102, . | 1.5 | 60 |
| 77 | Modeling of optical and energy performance of tungsten-oxide-based electrochromic windows including their intermediate states. Solar Energy Materials and Solar Cells, 2013, 108, 129-135. | 3.0 | 32 |
| 78 | Ion Charge State Distributions of Al and Cr in Cathodic Arc Plasmas From Composite Cathodes in Vacuum, Argon, Nitrogen, and Oxygen. IEEE Transactions on Plasma Science, 2013, 41, 1929-1937. | 0.6 | 20 |
| 79 | Drifting localization of ionization runaway: Unraveling the nature of anomalous transport in high power impulse magnetron sputtering. Journal of Applied Physics, 2012, 111, 053304. | 1.1 | 143 |
| 80 | Charge state distributions of Al and Cr cathodic arc plasmas. , 2012, , . | | 1 |
| 81 | Improved structural and electrical properties of thin ZnO:Al films by dc filtered cathodic arc deposition. Journal of Materials Research, 2012, 27, 857-862. | 1.2 | 4 |
| 82 | Plasma flares in high power impulse magnetron sputtering. Applied Physics Letters, 2012, 101, . | 1.5 | 45 |
| 83 | Thermal decomposition and fractal properties of sputter-deposited platinum oxide thin films. Journal of Materials Research, 2012, 27, 829-836. | 1.2 | 13 |
| 84 | The â€˜recycling trapâ€™: a generalized explanation of discharge runaway in high-power impulse magnetron sputtering. Journal Physics D: Applied Physics, 2012, 45, 012003. | 1.3 | 85 |
| 85 | Determining the nonparabolicity factor of the CdO conduction band using indium doping and the Drude theory. Journal Physics D: Applied Physics, 2012, 45, 425302. | 1.3 | 42 |
| 86 | The evolution of ion charge states in cathodic vacuum arc plasmas: a review. Plasma Sources Science and Technology, 2012, 21, 035014. | 1.3 | 62 |
| 87 | Phase transitions in vacuum arcs in the context of liquid metal arc sources. , 2012, , . | | 3 |
| 88 | Self-organization and self-limitation in high power impulse magnetron sputtering. Applied Physics Letters, 2012, 100, . | 1.5 | 73 |
| 89 | Plasma potential mapping of high power impulse magnetron sputtering discharges. Journal of Applied Physics, 2012, 111, . | 1.1 | 75 |
| 90 | Modelling of target effects in reactive HIPIMS. IOP Conference Series: Materials Science and Engineering, 2012, 39, 012008. | 0.3 | 7 |

| # | Article | IF | Citations |
|---|---|---|---|
| 91 | Boron-rich plasma by high power impulse magnetron sputtering of lanthanum hexaboride. Journal of Applied Physics, 2012, 112, . | 1.1 | 8 |
| 92 | Efficient, Low Cost Synthesis of Sodium Platinum Bronze Na<sub>x</sub>Pt<sub>3</sub>O<sub>4</sub>. Chemistry of Materials, 2012, 24, 2429-2432. | 3.2 | 6 |
| 93 | Gas rarefaction and the time evolution of long high-power impulse magnetron sputtering pulses. Plasma Sources Science and Technology, 2012, 21, 045004. | 1.3 | 82 |
| 94 | Evaluation of species-specific score cutoff values of routinely isolated clinically relevant bacteria using a direct smear preparation for matrix-assisted laser desorption/ionization time-of-flight mass spectrometry-based bacterial identification. European Journal of Clinical Microbiology and Infectious Diseases, 2012, 31, 1109-1119. | 1.3 | 33 |
| 95 | Analysis of Bulk and Thin Film Model Samples Intended for Investigating the Strain Sensitivity of Niobium-Tin. IEEE Transactions on Applied Superconductivity, 2011, 21, 2550-2553. | 1.1 | 6 |
| 96 | Achieving high mobility ZnOâ€‰:â€‰Al at very high growth rates by dc filtered cathodic arc deposition. Journal Physics D: Applied Physics, 2011, 44, 232003. | 1.3 | 34 |
| 97 | A synchronized emissive probe for time-resolved plasma potential measurements of pulsed discharges. Review of Scientific Instruments, 2011, 82, 093505. | 0.6 | 10 |
| 98 | Dynamically Modulating the Surface Plasmon Resonance of Doped Semiconductor Nanocrystals. Nano Letters, 2011, 11, 4415-4420. | 4.5 | 491 |
| 99 | Measurements of the Ion Species of Cathodic Arc Plasma in an Axial Magnetic Field. IEEE Transactions on Plasma Science, 2011, 39, 1272-1276. | 0.6 | 7 |
| 100 | Dense Metal Plasma in a Solenoid for Ion Beam Neutralization. IEEE Transactions on Plasma Science, 2011, 39, 1386-1393. | 0.6 | 11 |
| 101 | Chemistry, phase formation, and catalytic activity of thin palladium-containing oxide films synthesized by plasma-assisted physical vapor deposition. Surface and Coatings Technology, 2011, 205, S171-S177. | 2.2 | 33 |
| 102 | Discharge physics of high power impulse magnetron sputtering. Surface and Coatings Technology, 2011, 205, S1-S9. | 2.2 | 225 |
| 103 | A Plasma Lens for Magnetron Sputtering. IEEE Transactions on Plasma Science, 2011, 39, 2528-2529. | 0.6 | 18 |
| 104 | Identification of Ternary Phases in TiBC/aâ€Œ Nanocomposite Thin Films: Influence on the Electrical and Optical Properties. Plasma Processes and Polymers, 2011, 8, 579-588. | 1.6 | 10 |
| 105 | Optical properties of ferromagnetic ytterbiumâ€doped IIIâ€nitride epilayers. Physica Status Solidi C: Current Topics in Solid State Physics, 2011, 8, 2185-2187. | 0.8 | 4 |
| 106 | Preparation of high transmittance ZnO:Al film by pulsed filtered cathodic arc technology and rapid thermal annealing. Applied Surface Science, 2011, 257, 7019-7022. | 3.1 | 8 |
| 107 | Hollow Plasma in a Solenoid. IEEE Transactions on Plasma Science, 2011, 39, 2888-2889. | 0.6 | 1 |
| 108 | High Rate Deposition of High Quality ZnO:Al by Filtered Cathodic Arc. Materials Research Society Symposia Proceedings, 2011, 1315, 1. | 0.1 | 1 |

| # | Article | IF | Citations |
|---|---|---|---|
| 109 | Epitaxy of Ultrathin NiSi2 Films with Predetermined Thickness. Electrochemical and Solid-State Letters, 2011, 14, H268. | 2.2 | 21 |
| 110 | Optical studies of strained InGaN/GaN quantum structures implanted with europium for red light emitting diodes. , 2011, , . | | 0 |
| 111 | High quality ZnO:Al transparent conducting oxide films synthesized by pulsed filtered cathodic arc deposition. Thin Solid Films, 2010, 518, 3313-3319. | 0.8 | 48 |
| 112 | A structure zone diagram including plasma-based deposition and ion etching. Thin Solid Films, 2010, 518, 4087-4090. | 0.8 | 641 |
| 113 | High power impulse magnetron sputtering and related discharges: Scalable plasma sources for plasma-based ion implantation and deposition. Surface and Coatings Technology, 2010, 204, 2864-2868. | 2.2 | 51 |
| 114 | Optical and magnetic properties of GaN epilayers implanted with ytterbium. Journal of Rare Earths, 2010, 28, 931-935. | 2.5 | 10 |
| 115 | A self-sputtering ion source: A new approach to quiescent metal ion beams. Review of Scientific Instruments, 2010, 81, 02B306. | 0.6 | 10 |
| 116 | Resonant Inelastic Scattering Spectra of Free Molecules with Vibrational Resolution. Physical Review Letters, 2010, 104, 193002. | 2.9 | 126 |
| 117 | Beneficial silver: antibacterial nanocomposite Ag-DLC coating to reduce osteolysis of orthopaedic implants. Journal of Physics: Conference Series, 2010, 252, 012005. | 0.3 | 6 |
| 118 | Ion acceleration and cooling in gasless self-sputtering. Applied Physics Letters, 2010, 97, . | 1.5 | 21 |
| 119 | On the deactivation of the dopant and electronic structure in reactively sputtered transparent Al-doped ZnO thin films. Journal Physics D: Applied Physics, 2010, 43, 132003. | 1.3 | 34 |
| 120 | Compression and strong rarefaction in high power impulse magnetron sputtering discharges. Journal of Applied Physics, 2010, 108, . | 1.1 | 73 |
| 121 | Origin of the Delayed Current Onset in High-Power Impulse Magnetron Sputtering. IEEE Transactions on Plasma Science, 2010, 38, 3028-3034. | 0.6 | 71 |
| 122 | Deposition rates of high power impulse magnetron sputtering: Physics and economics. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2010, 28, 783-790. | 0.9 | 172 |
| 123 | Distance-dependent plasma composition and ion energy in high power impulse magnetron sputtering. Journal Physics D: Applied Physics, 2010, 43, 275204. | 1.3 | 23 |
| 124 | Supersonic metal plasma impact on a surface: an optical investigation of the pre-surface region. Journal Physics D: Applied Physics, 2010, 43, 135201. | 1.3 | 7 |
| 125 | Antibacterial efficacy of advanced silver-amorphous carbon coatings deposited using the pulsed dual cathodic arc technique. Journal of Physics: Conference Series, 2010, 252, 012012. | 0.3 | 17 |
| 126 | Energetic deposition of metal ions: observation of self-sputtering and limited sticking for off-normal angles of incidence. Journal Physics D: Applied Physics, 2010, 43, 065206. | 1.3 | 18 |

| # | Article | IF | Citations |
|---|---|---|---|
| 127 | Unfiltered and Filtered Cathodic Arc Deposition. , 2010, , 466-531. | | 14 |
| 128 | Ion species and charge states of vacuum arc plasma with gas feed and longitudinal magnetic field. , 2010, , . | | 0 |
| 129 | A seemingly simple task: Filling a solenoid volume in vacuum with dense plasma. , 2010, , . | | 0 |
| 130 | Broad, intense, quiescent beam of singly charged metal ions obtained by extraction from self-sputtering plasma far above the runaway threshold. Journal of Applied Physics, 2009, 106, 023306. | 1.1 | 12 |
| 131 | Structural and spectroscopic studies of InGaN/GaN quantum structures implanted with rare earth ions. , 2009, , . | | 0 |
| 132 | Physical limits for high ion charge states in pulsed discharges in vacuum. Journal of Applied Physics, 2009, 105, 043303. | 1.1 | 16 |
| 133 | A discussion on the absence of plasma in spark plasma sintering. Scripta Materialia, 2009, 60, 835-838. | 2.6 | 204 |
| 134 | Electronic structure and conductivity of nanocomposite metal (Au, Ag, Cu, Mo)-containing amorphous carbon films. Solid State Sciences, 2009, 11, 1742-1746. | 1.5 | 32 |
| 135 | Impact of Annealing on the Conductivity of Amorphous Carbon Films Incorporating Copper and Gold Nanoparticles Deposited by Pulsed Dual Cathodic Arc. Plasma Processes and Polymers, 2009, 6, S438. | 1.6 | 9 |
| 136 | A space-charge-neutralizing plasma for beam drift compression. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2009, 606, 22-30. | 0.7 | 23 |
| 137 | Progress in beam focusing and compression for warm-dense matter experiments. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2009, 606, 75-82. | 0.7 | 45 |
| 138 | Surface transformation of graphite or diamond following Highly Charged Ion irradiation. Nuclear Instruments & Methods in Physics Research B, 2009, 267, 678-682. | 0.6 | 2 |
| 139 | Electronic Structure of Water Molecules Confined in a Micelle Lattice. Journal of Physical Chemistry B, 2009, 113, 8201-8205. | 1.2 | 20 |
| 140 | Local Electronic Structure of Functional Groups in Glycine As Anion, Zwitterion, and Cation in Aqueous Solution. Journal of Physical Chemistry B, 2009, 113, 16002-16006. | 1.2 | 38 |
| 141 | Spectra and energy levels of Yb3+ in AlN. Journal of Applied Physics, 2009, 106, 013106. | 1.1 | 24 |
| 142 | Evolution of the plasma composition of a high power impulse magnetron sputtering system studied with a time-of-flight spectrometer. Journal of Applied Physics, 2009, 105, . | 1.1 | 37 |
| 143 | Self-Sputtering Far above the Runaway Threshold: An Extraordinary Metal-Ion Generator. Physical Review Letters, 2009, 102, 045003. | 2.9 | 72 |
| 144 | Plasma â€œanti-assistanceâ€•and â€œself-assistanceâ€•to high power impulse magnetron sputtering. Journal of Applied Physics, 2009, 105, . | 1.1 | 38 |

| # | Article | IF | Citations |
|---|---|---|---|
| 145 | Simulations and experiments of intense ion beam current density compression in space and time. Physics of Plasmas, 2009, 16, 056701. | 0.7 | 15 |
| 146 | Deep oxidation of methane on particles derived from YSZ-supported Pdâ€“Pt-(O) coatings synthesized by Pulsed Filtered Cathodic Arc. Catalysis Communications, 2009, 10, 1410-1413. | 1.6 | 9 |
| 147 | Functionalization of hydrogen-free diamond-like carbon films using open-air dielectric barrier discharge atmospheric plasma treatments. Applied Surface Science, 2008, 254, 5323-5328. | 3.1 | 16 |
| 148 | Electrochromically switched, gas-reservoir metal hydride devices with application to energy-efficient windows. Thin Solid Films, 2008, 517, 1021-1026. | 0.8 | 16 |
| 149 | Physics of plasmaâ€based ion implantation & deposition (PBIID) and high power impulse magnetron sputtering (HIPIMS): A comparison. Physica Status Solidi (A) Applications and Materials Science, 2008, 205, 965-970. | 0.8 | 8 |
| 150 | Comparative surface and nano-tribological characteristics of nanocomposite diamond-like carbon thin films doped by silver. Applied Surface Science, 2008, 255, 2551-2556. | 3.1 | 174 |
| 151 | Structure and properties of silver-containing a-C(H) films deposited by plasma immersion ion implantation. Surface and Coatings Technology, 2008, 202, 3675-3682. | 2.2 | 87 |
| 152 | Coalescence of magnetron-sputtered silver islands affected by transition metal seeding (Ni, Cr, Nb, Zr,) Tj ETQq0 0 0 rgBT /Overlock 10 T | 0.8 | 38 |
| 153 | MeV-ion beam analysis of the interface between filtered cathodic arc-deposited a-carbon and single crystalline silicon. Nuclear Instruments & Methods in Physics Research B, 2008, 266, 5175-5179. | 0.6 | 2 |
| 154 | Macroparticles. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 265-298. | 0.1 | 0 |
| 155 | Reactive Deposition. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 409-428. | 0.1 | 1 |
| 156 | The absence of plasma in â€œspark plasma sinteringâ€. Journal of Applied Physics, 2008, 104, . | 1.1 | 142 |
| 157 | Film Deposition by Energetic Condensation. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 363-407. | 0.1 | 8 |
| 158 | The Physics of Cathode Processes. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 75-174. | 0.1 | 7 |
| 159 | Self-sputtering runaway in high power impulse magnetron sputtering: The role of secondary electrons and multiply charged metal ions. Applied Physics Letters, 2008, 92, . | 1.5 | 84 |
| 160 | Sputtering in vacuum: A technology for ultraclean metallization and space propulsion. , 2008, , . | | 1 |
| 161 | Gasless sputtering: Opportunities for ultraclean metallization, coatings in space, and propulsion. Applied Physics Letters, 2008, 92, . | 1.5 | 71 |
| 162 | The electronic structure of tungsten oxide thin films prepared by pulsed cathodic arc deposition and plasma-assisted pulsed magnetron sputtering. Journal of Physics Condensed Matter, 2008, 20, 175216. | 0.7 | 5 |

| # | Article | IF | Citations |
|---|---|---|---|
| 163 | Cathodic Arcs. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , . | 0.1 | 443 |
| 164 | Spatial distribution of average charge state and deposition rate in high power impulse magnetron sputtering of copper. Journal Physics D: Applied Physics, 2008, 41, 135210. | 1.3 | 42 |
| 165 | A Theoretical Analysis of Vacuum Arc Thruster and Vacuum Arc Ion Thruster Performance. IEEE Transactions on Plasma Science, 2008, 36, 2167-2179. | 0.6 | 76 |
| 166 | Electrical properties of a-C: Mo films produced by dual-cathode filtered cathodic arc plasma deposition. Diamond and Related Materials, 2008, 17, 2080-2083. | 1.8 | 13 |
| 167 | A summary of recent experimental research on ion energy and charge states of pulsed vacuum arcs. , 2008, , . | | 5 |
| 168 | High charge state ions extracted from metal plasmas in the transition regime from vacuum spark to high current vacuum arc. , 2008, , . | | 1 |
| 169 | Extractable, elevated ion charge states in the transition regime from vacuum sparks to high current vacuum arcs. Applied Physics Letters, 2008, 92, . | 1.5 | 43 |
| 170 | Studies of III-Nitride Superlattice Structures Implanted with Lanthanide Ions. Materials Research Society Symposia Proceedings, 2008, 1111, 1. | 0.1 | 3 |
| 171 | Measurements of the asymmetric dynamic sheath around a pulse biased sphere immersed in flowing metal plasma. Plasma Sources Science and Technology, 2008, 17, 035030. | 1.3 | 2 |
| 172 | Some Applications of Cathodic Arc Coatings. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 429-490. | 0.1 | 1 |
| 173 | Temporal development of ion beam mean charge state in pulsed vacuum arc ion sources. Review of Scientific Instruments, 2008, 79, 02B301. | 0.6 | 13 |
| 174 | Inverted end-Hall-type low-energy high-current gaseous ion source. Review of Scientific Instruments, 2008, 79, 02B302. | 0.6 | 3 |
| 175 | A study of vacuum arc ion velocities using a linear set of probes. Journal Physics D: Applied Physics, 2008, 41, 205210. | 1.3 | 12 |
| 176 | Observation of Ti4+ ions in a high power impulse magnetron sputtering plasma. Applied Physics Letters, 2008, 93, . | 1.5 | 56 |
| 177 | Effects of ozone oxidation on interfacial and dielectric properties of thin HfO2 films. Journal of Applied Physics, 2008, 104, 054117. | 1.1 | 14 |
| 178 | Modification of Surface and Tribological Properties of DLC Films by Adding Silver Content. , 2008, , . | | 0 |
| 179 | Cathodic Arc Sources. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 227-263. | 0.1 | 6 |
| 180 | The Interelectrode Plasma. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 175-225. | 0.1 | 1 |

| # | Article | IF | Citations |
|---|---|---|---|
| 181 | A Brief History of Cathodic Arc Coating. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 7-74. | 0.1 | 1 |
| 182 | Macroparticle Filters. Springer Series on Atomic, Optical, and Plasma Physics, 2008, , 299-362. | 0.1 | 1 |
| 183 | Low-energy linear oxygen plasma source. Review of Scientific Instruments, 2007, 78, 043304. | 0.6 | 10 |
| 184 | Charge-state-resolved ion energy distribution functions of cathodic vacuum arcs: A study involving the plasma potential and biased plasmas. Journal of Applied Physics, 2007, 101, 043304. | 1.1 | 39 |
| 185 | Filtered cathodic arc deposition with ion-species-selective bias. Review of Scientific Instruments, 2007, 78, 063901. | 0.6 | 28 |
| 186 | Puzzling differences in bismuth and lead plasmas: Evidence for the significant role of neutrals in cathodic vacuum arcs. Applied Physics Letters, 2007, 91, . | 1.5 | 25 |
| 187 | Combined filtered cathodic arc etching pretreatmentâ€“magnetron sputter deposition of highly adherent CrN films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2007, 25, 543-550. | 0.9 | 20 |
| 188 | High power impulse magnetron sputtering: Current-voltage-time characteristics indicate the onset of sustained self-sputtering. Journal of Applied Physics, 2007, 102, . | 1.1 | 287 |
| 189 | Production of neutrals and their effects on the ion charge states in cathodic vacuum arc plasmas. Journal of Applied Physics, 2007, 102, . | 1.1 | 53 |
| 190 | Cathodic Vacuum Arc Plasma of Thallium. IEEE Transactions on Plasma Science, 2007, 35, 516-517. | 0.6 | 5 |
| 191 | Source of Low-Energy High-Current Gaseous Ion Flow Based on a Discharge with Electron Injection. , 2007, , . | | 0 |
| 192 | Plasma biasing to control the growth conditions of diamond-like carbon. Surface and Coatings Technology, 2007, 201, 4628-4632. | 2.2 | 21 |
| 193 | Physical properties of erbium implanted tungsten oxide films deposited by reactive dual magnetron sputtering. Thin Solid Films, 2007, 515, 5264-5269. | 0.8 | 14 |
| 194 | Mo-containing tetrahedral amorphous carbon deposited by dual filtered cathodic vacuum arc with selective pulsed bias voltage. Nuclear Instruments & Methods in Physics Research B, 2007, 259, 867-870. | 0.6 | 28 |
| 195 | Structural and optical evaluation of WOxNy films deposited by reactive magnetron sputtering. Journal of Physics and Chemistry of Solids, 2007, 68, 2227-2232. | 1.9 | 8 |
| 196 | Metal plasmas for the fabrication of nanostructures. Journal Physics D: Applied Physics, 2007, 40, 2272-2284. | 1.3 | 73 |
| 197 | Neutralized drift compression experiments with a high-intensity ion beam. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2007, 577, 223-230. | 0.7 | 11 |
| 198 | Material-dependent high-frequency current fluctuations of cathodic vacuum arcs: Evidence for the ecton cutoff of the fractal model. Journal of Applied Physics, 2006, 99, 103301. | 1.1 | 13 |

| # | Article | IF | Citations |
|---|---|---|---|
| 199 | Charge state dependence of cathodic vacuum arc ion energy and velocity distributions. Applied Physics Letters, 2006, 89, 141502. | 1.5 | 28 |
| 200 | Luminescence Properties of Dy Implanted AlN Thin Films. ECS Meeting Abstracts, 2006, , . | 0.0 | 0 |
| 201 | Smoothing of ultrathin silver films by transition metal seeding. Solid State Communications, 2006, 140, 225-229. | 0.9 | 67 |
| 202 | Structural, optical, and electrical properties of WOx(Ny) films deposited by reactive dual magnetron sputtering. Surface and Coatings Technology, 2006, 201, 2977-2983. | 2.2 | 43 |
| 203 | Determination of the specific ion erosion of the vacuum arc cathode by measuring the total ion current from the discharge plasma. Technical Physics, 2006, 51, 1311-1315. | 0.2 | 11 |
| 204 | Physics of arcing, and implications to sputter deposition. Thin Solid Films, 2006, 502, 22-28. | 0.8 | 78 |
| 205 | Fourier Analysis of Fast Vacuum Arc Parameters. , 2006, , . | | 1 |
| 206 | Measurement of total ion current from vacuum arc plasma sources. Review of Scientific Instruments, 2006, 77, 03B504. | 0.6 | 22 |
| 207 | Biocompatible Silver-containing a-C:H and a-C coatings: A Comparative Study. Materials Research Society Symposia Proceedings, 2006, 950, 1. | 0.1 | 3 |
| 208 | Influence of argon and oxygen on charge-state-resolved ion energy distributions of filtered aluminum arcs. Journal of Applied Physics, 2006, 99, 123303. | 1.1 | 34 |
| 209 | Neutralized transport experiment. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2005, 544, 225-235. | 0.7 | 23 |
| 210 | Plasma and ion sources in large area coating: A review. Surface and Coatings Technology, 2005, 200, 1893-1906. | 2.2 | 123 |
| 211 | Instability of a low-pressure hollow-cathode discharge in a magnetic field. Plasma Physics Reports, 2005, 31, 978-983. | 0.3 | 9 |
| 212 | Charge-state-resolved ion energy distributions of aluminum vacuum arcs in the absence and presence of a magnetic field. Journal of Applied Physics, 2005, 97, 103306. | 1.1 | 35 |
| 213 | Time-dependence of ion charge State distributions of vacuum arcs: an interpretation involving atoms and charge exchange collisions. IEEE Transactions on Plasma Science, 2005, 33, 205-209. | 0.6 | 28 |
| 214 | Drift Compression of an Intense Neutralized Ion Beam. Physical Review Letters, 2005, 95, 234801. | 2.9 | 118 |
| 215 | Time and material dependence of the voltage noise generated by cathodic vacuum arcs. Journal Physics D: Applied Physics, 2005, 38, 4184-4190. | 1.3 | 21 |
| 216 | A Source of Ultra-Low-Energy High Intensity Gaseous Ions Based on Discharge with Electron Injection. IEEE International Conference on Plasma Science, 2005, , . | 0.0 | 0 |

| # | Article | IF | Citations |
|---|---|---|---|
| 217 | Cathodic arcs: Fractal voltage and cohesive energy rule. Applied Physics Letters, 2005, 86, 211503. | 1.5 | 51 |
| 218 | Measurements of the total ion flux from vacuum arc cathode spots. IEEE Transactions on Plasma Science, 2005, 33, 1532-1536. | 0.6 | 84 |
| 219 | The fractal nature of vacuum arc cathode spots. IEEE Transactions on Plasma Science, 2005, 33, 1456-1464. | 0.6 | 67 |
| 220 | Plasma-based ion implantation and deposition: a review of physics, technology, and applications. IEEE Transactions on Plasma Science, 2005, 33, 1944-1959. | 0.6 | 156 |
| 221 | Ion charge state fluctuations in vacuum arcs. Journal Physics D: Applied Physics, 2005, 38, 1021-1028. | 1.3 | 13 |
| 222 | The kinetic energy of carbon ions in vacuum arc plasmas: A comparison of measuring techniques. Journal of Applied Physics, 2004, 96, 970-974. | 1.1 | 15 |
| 223 | Results on intense beam focusing and neutralization from the neutralized beam experiment. Physics of Plasmas, 2004, 11, 2890-2898. | 0.7 | 64 |
| 224 | Observation of self-sputtering in energetic condensation of metal ions. Applied Physics Letters, 2004, 85, 6137-6139. | 1.5 | 29 |
| 225 | Charge state and time resolved plasma composition of a pulsed zirconium arc in a nitrogen environment. Journal of Applied Physics, 2004, 96, 4793-4799. | 1.1 | 14 |
| 226 | Effect of Ion Mass and Charge State on Transport of Vacuum Arc Plasmas Through a Biased Magnetic Filter. IEEE Transactions on Plasma Science, 2004, 32, 433-439. | 0.6 | 9 |
| 227 | Insights into â€œnear-frictionless carbon filmsâ€• Journal of Applied Physics, 2004, 95, 7765-7771. | 1.1 | 40 |
| 228 | Fundamentals of pulsed plasmas for materials processing. Surface and Coatings Technology, 2004, 183, 301-311. | 2.2 | 116 |
| 229 | Some effects of magnetic field on a hollow cathode ion source. Review of Scientific Instruments, 2004, 75, 1030-1033. | 0.6 | 13 |
| 230 | Design and characterization of a neutralized-transport experiment for heavy-ion fusion. Physical Review Special Topics: Accelerators and Beams, 2004, 7, . | 1.8 | 36 |
| 231 | Asymmetric injection of cathodic arc plasma into a macroparticle filter. Journal of Applied Physics, 2004, 95, 7602-7606. | 1.1 | 4 |
| 232 | Tracking down the origin of arc plasma science I. early pulsed and oscillating discharges. IEEE Transactions on Plasma Science, 2003, 31, 1052-1059. | 0.6 | 21 |
| 233 | Tracking down the origin of arc plasma science-II. early continuous discharges. IEEE Transactions on Plasma Science, 2003, 31, 1060-1069. | 0.6 | 31 |
| 234 | Bias and self-bias of magnetic macroparticle filters for cathodic arc plasmas. Journal of Applied Physics, 2003, 93, 8890-8897. | 1.1 | 18 |

| # | Article | IF | Citations |
|---|---|---|---|
| 235 | Flexible system for multiple plasma immersion ion implantation-deposition processes. Review of Scientific Instruments, 2003, 74, 5137-5140. | 0.6 | 9 |
| 236 | Temporal development of the composition of Zr and Cr cathodic arc plasma streams in a N2 environment. Journal of Applied Physics, 2003, 94, 1414-1419. | 1.1 | 20 |
| 237 | Time-resolved emittance of a bismuth ion beam from a pulsed vacuum arc ion source. Journal of Applied Physics, 2003, 93, 2298-2300. | 1.1 | 10 |
| 238 | Coalescence of nanometer silver islands on oxides grown by filtered cathodic arc deposition. Applied Physics Letters, 2003, 82, 1634-1636. | 1.5 | 53 |
| 239 | Ion energy distribution functions of vacuum arc plasmas. Journal of Applied Physics, 2003, 93, 1899-1906. | 1.1 | 81 |
| 240 | Plasma chemistry fluctuations in a reactive arc plasma in the presence of magnetic fields. Applied Physics Letters, 2002, 80, 4109-4111. | 1.5 | 9 |
| 241 | Atomic scale heating in cathodic arc plasma deposition. Applied Physics Letters, 2002, 80, 1100-1102. | 1.5 | 98 |
| 242 | Angularly resolved measurements of ion energy of vacuum arc plasmas. Applied Physics Letters, 2002, 80, 2457-2459. | 1.5 | 44 |
| 243 | Magnetic field effect on the sheath thickness in plasma immersion ion implantation. Applied Physics Letters, 2002, 81, 1183-1185. | 1.5 | 48 |
| 244 | Developing high brightness beams for heavy ion driven inertial fusion. Review of Scientific Instruments, 2002, 73, 1084-1086. | 0.6 | 2 |
| 245 | Reducing ion-beam noise of vacuum arc ion sources. Review of Scientific Instruments, 2002, 73, 732-734. | 0.6 | 9 |
| 246 | Further development of low noise vacuum arc ion source. Review of Scientific Instruments, 2002, 73, 735-737. | 0.6 | 13 |
| 247 | Inductive energy storage driven vacuum arc thruster. Review of Scientific Instruments, 2002, 73, 925-927. | 0.6 | 69 |
| 248 | Two-dimensional sample temperature modeling in separation by plasma implantation of oxygen (SPIMOX) process. IEEE Transactions on Plasma Science, 2002, 30, 423-427. | 0.6 | 1 |
| 249 | Ion flux from vacuum arc cathode spots in the absence and presence of a magnetic field. Journal of Applied Physics, 2002, 91, 4824-4832. | 1.1 | 342 |
| 250 | Energetic deposition using filtered cathodic arc plasmas. Vacuum, 2002, 67, 673-686. | 1.6 | 92 |
| 251 | From plasma immersion ion implantation to deposition: a historical perspective on principles and trends. Surface and Coatings Technology, 2002, 156, 3-12. | 2.2 | 79 |
| 252 | Imaging the separation of cathodic arc plasma and macroparticles in curved magnetic filters. IEEE Transactions on Plasma Science, 2002, 30, 108-109. | 0.6 | 16 |

| # | Article | IF | Citations |
|---|---|---|---|
| 253 | Cohesive Energy Rule for Vacuum Arcs. , 2002, , 1-14. | | 12 |
| 254 | Emission Methods of Experimental Investigations of Ion Velocities in Vacuum Arc Plasmas. , 2002, , 105-113. | | 0 |
| 255 | Magnetic system for producing uniform coatings using a filtered cathodic arc. Plasma Sources Science and Technology, 2001, 10, 606-613. | 1.3 | 16 |
| 256 | Magnetic-field-dependent plasma composition of a pulsed aluminum arc in an oxygen ambient. Applied Physics Letters, 2001, 78, 150-152. | 1.5 | 29 |
| 257 | Synthesis of Ultrathin Ta-C Films by Twist-Filtered Cathodic Arc Carbon Plasmas. Materials Research Society Symposia Proceedings, 2001, 675, 1. | 0.1 | 7 |
| 258 | Compact vacuum arc micro-thruster for small satellite systems. , 2001, , . | | 8 |
| 259 | Ultrathin diamond-like carbon films deposited by filtered carbon vacuum arcs. IEEE Transactions on Plasma Science, 2001, 29, 768-775. | 0.6 | 55 |
| 260 | A periodic table of ion charge-state distributions observed in the transition region between vacuum sparks and vacuum arcs. IEEE Transactions on Plasma Science, 2001, 29, 393-398. | 0.6 | 54 |
| 261 | Correlation between cathode properties, burning voltage, and plasma parameters of vacuum arcs. Journal of Applied Physics, 2001, 89, 7764-7771. | 1.1 | 95 |
| 262 | Guest editorial special issue on vacuum discharge plasmas. IEEE Transactions on Plasma Science, 2001, 29, 654-656. | 0.6 | 0 |
| 263 | Regulation of the Î±â€secretase ADAM10 by its prodomain and proprotein convertases. FASEB Journal, 2001, 15, 1837-1839. | 0.2 | 220 |
| 264 | Arc-discharge ion sources for heavy ion fusion. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2001, 464, 569-575. | 0.7 | 17 |
| 265 | Recent advances in high current vacuum arc ion sources for heavy ion fusion. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2001, 464, 576-581. | 0.7 | 4 |
| 266 | Width, structure and stability of sheaths in metal plasma immersion ion implantation and deposition: measurements and analytical considerations. Surface and Coatings Technology, 2001, 136, 85-92. | 2.2 | 50 |
| 267 | Measurements of secondary electrons emitted from conductive substrates under high-current metal ion bombardment. Surface and Coatings Technology, 2001, 136, 111-116. | 2.2 | 15 |
| 268 | Generation of Multiply Charged Ions in the Plasma of a Vacuum Arc Discharge. Russian Physics Journal, 2001, 44, 912-920. | 0.2 | 6 |
| 269 | MBE growth of (In)GaAsN on GaAs using a constricted DC plasma source. Semiconductor Science and Technology, 2001, 16, 413-419. | 1.0 | 4 |
| 270 | Energetics of vacuum arc cathode spots. Applied Physics Letters, 2001, 78, 2837-2839. | 1.5 | 21 |

| # | Article | IF | Citations |
|---|---|---|---|
| 271 | Review of cathodic arc deposition technology at the start of the new millennium. Surface and Coatings Technology, 2000, 133-134, 78-90. | 2.2 | 203 |
| 272 | Twist filter for the removal of macroparticles from cathodic arc plasmas. Surface and Coatings Technology, 2000, 133-134, 96-100. | 2.2 | 42 |
| 273 | Chopping effect observed at cathodic arc initiation. IEEE Transactions on Plasma Science, 2000, 28, 1303-1304. | 0.6 | 13 |
| 274 | Effect of multiple current spikes on the enhancement of ion charge states of vacuum arc plasmas. Journal of Applied Physics, 2000, 87, 8345-8350. | 1.1 | 38 |
| 275 | Breakdown of the high-voltage sheath in metal plasma immersion ion implantation. Applied Physics Letters, 2000, 76, 28-30. | 1.5 | 28 |
| 276 | Enhanced ion charge states in vacuum arc plasmas using a â€œcurrent spikeâ€•method. Review of Scientific Instruments, 2000, 71, 701-703. | 0.6 | 44 |
| 277 | Pulsed vacuum-arc ion source operated with a â€œtriggerlessâ€•arc initiation method. Review of Scientific Instruments, 2000, 71, 827-829. | 0.6 | 56 |
| 278 | Magnetic-field-dependent plasma composition of a pulsed arc in a high-vacuum ambient. Applied Physics Letters, 2000, 76, 1531-1533. | 1.5 | 18 |
| 279 | Ion velocities in vacuum arc plasmas. Journal of Applied Physics, 2000, 88, 5618-5622. | 1.1 | 229 |
| 280 | Temporal development of the plasma composition of a pulsed aluminum plasma stream in the presence of oxygen. Applied Physics Letters, 1999, 75, 612-614. | 1.5 | 32 |
| 281 | Efficient, compact power supply for repetitively pulsed, â€œtriggerlessâ€•cathodic arcs. Review of Scientific Instruments, 1999, 70, 4532-4535. | 0.6 | 29 |
| 282 | Recent advances in surface processing with metal plasma and ion beams. Surface and Coatings Technology, 1999, 112, 271-277. | 2.2 | 60 |
| 283 | Approaches to rid cathodic arc plasmas of macro- and nanoparticles: a review. Surface and Coatings Technology, 1999, 120-121, 319-330. | 2.2 | 206 |
| 284 | Vacuum-arc-generated macroparticles in the nanometer range. IEEE Transactions on Plasma Science, 1999, 27, 1030-1033. | 0.6 | 19 |
| 285 | Velocity distribution of carbon macroparticles generated by pulsed vacuum arcs. Plasma Sources Science and Technology, 1999, 8, 567-571. | 1.3 | 30 |
| 286 | Ion charge state distributions of alloy-cathode vacuum arc plasmas. IEEE Transactions on Plasma Science, 1999, 27, 911-914. | 0.6 | 19 |
| 287 | Paragenetic suppressors of suppressor genes - a new class of oncodeterminants. Journal of Cancer Research and Clinical Oncology, 1999, 125, 123-133. | 1.2 | 10 |
| 288 | Evaluation of the plasma distribution of a quasi-linear constricted plasma source. IEEE Transactions on Plasma Science, 1999, 27, 82-83. | 0.6 | 5 |

| # | Article | IF | Citations |
|---|---|---|---|
| 289 | Free-boundary vacuum arc plasma jet expansion in a curved magnetic field. IEEE Transactions on Plasma Science, 1999, 27, 613-619. | 0.6 | 14 |
| 290 | Plasma fluctuations, local partial Saha equilibrium, and the broadening of vacuum-arc ion charge state distributions. IEEE Transactions on Plasma Science, 1999, 27, 1060-1067. | 0.6 | 31 |
| 291 | Characterization of a linear venetian-blind macroparticle filter for cathodic vacuum arcs. IEEE Transactions on Plasma Science, 1999, 27, 1197-1202. | 0.6 | 19 |
| 292 | Low-energy ion assisted deposition of epitaxial gallium nitride films. Nuclear Instruments & Methods in Physics Research B, 1999, 148, 406-410. | 0.6 | 6 |
| 293 | Designing advanced filters for macroparticle removal from cathodic arc plasmas. Plasma Sources Science and Technology, 1999, 8, 488-493. | 1.3 | 32 |
| 294 | Ion implantation post-processing of amorphous carbon films. Diamond and Related Materials, 1999, 8, 451-456. | 1.8 | 11 |
| 295 | Hydrogen uptake in alumina thin films synthesized from an aluminum plasma stream in an oxygen ambient. Applied Physics Letters, 1999, 74, 200-202. | 1.5 | 73 |
| 296 | Study of Low-Energy Ion Assisted Epitaxy of Gan Films: Influence of the Initial Growth Rate. Materials Research Society Symposia Proceedings, 1999, 585, 239. | 0.1 | 5 |
| 297 | Ion charge state distributions of pulsed vacuum arcs-interpretation of their temporal development. IEEE Transactions on Plasma Science, 1998, 26, 118-119. | 0.6 | 11 |
| 298 | Effect of the pulse repetition rate on the composition and ion charge-state distribution of pulsed vacuum arcs. IEEE Transactions on Plasma Science, 1998, 26, 220-226. | 0.6 | 51 |
| 299 | Surface resistivity tailoring of ceramics by metal ion implantation. Surface and Coatings Technology, 1998, 103-104, 46-51. | 2.2 | 15 |
| 300 | A filamentless ion source for materials processing. Review of Scientific Instruments, 1998, 69, 880-882. | 0.6 | 4 |
| 301 | Characterization of a low-energy constricted-plasma source. Review of Scientific Instruments, 1998, 69, 1340-1343. | 0.6 | 38 |
| 302 | `Triggerless' triggering of vacuum arcs. Journal Physics D: Applied Physics, 1998, 31, 584-587. | 1.3 | 119 |
| 303 | Streaming metal plasma generation by vacuum arc plasma guns. Review of Scientific Instruments, 1998, 69, 801-803. | 0.6 | 83 |
| 304 | Ion charge state distributions of pulsed vacuum arc plasmas in strong magnetic fields. Review of Scientific Instruments, 1998, 69, 1332-1335. | 0.6 | 46 |
| 305 | Results from energetic electron beam metal vapor vacuum arc and Z-discharge plasma metal vapor vacuum arc: Development of new sources of intense high charge state heavy-ion beams. Review of Scientific Instruments, 1998, 69, 798-800. | 0.6 | 16 |
| 306 | Interaction of vacuum-arc-generated macroparticles with a liquid surface. Applied Physics Letters, 1998, 73, 3199-3201. | 1.5 | 9 |

| # | Article | IF | Citations |
|---|---|---|---|
| 307 | Growth and decay of macroparticles: A feasible approach to clean vacuum arc plasmas?. Journal of Applied Physics, 1997, 82, 3679-3688. | 1.1 | 39 |
| 308 | Ion charge state distributions of vacuum arc plasmas: The origin of species. Physical Review E, 1997, 55, 969-981. | 0.8 | 300 |
| 309 | S-shaped magnetic macroparticle filter for cathodic arc deposition. IEEE Transactions on Plasma Science, 1997, 25, 670-674. | 0.6 | 69 |
| 310 | Vacuum-spark metal ion source based on a modified Marx generator. IEEE Transactions on Plasma Science, 1997, 25, 718-721. | 0.6 | 14 |
| 311 | Guest Editorial Special Issue On Vacuum Discharge Plasmas. IEEE Transactions on Plasma Science, 1997, 25, 519-520. | 0.6 | 1 |
| 312 | The effect of additional ion/plasma assistance in CNx-film deposition based on a filtered cathodic arc. Thin Solid Films, 1997, 311, 151-156. | 0.8 | 5 |
| 313 | High energy implantation with high-charge-state ions in a vacuum arc ion implanter. Nuclear Instruments & Methods in Physics Research B, 1997, 127-128, 779-781. | 0.6 | 9 |
| 314 | High energy metal ion implantation using a novel, broad-beam, Marx-generator-based ion source â€œMagisâ€• Nuclear Instruments & Methods in Physics Research B, 1997, 127-128, 992-995. | 0.6 | 5 |
| 315 | Macroparticle filtering of high-current vacuum arc plasmas. IEEE Transactions on Plasma Science, 1997, 25, 660-664. | 0.6 | 54 |
| 316 | Metal plasma immersion ion implantation and deposition: a review. Surface and Coatings Technology, 1997, 93, 158-167. | 2.2 | 239 |
| 317 | Optics of Human Skin: UV Effects Investigated with Dye Lasers. , 1997, , 205-210. | | 0 |
| 318 | Diamond growth on hard carbon films. Diamond and Related Materials, 1996, 5, 1080-1086. | 1.8 | 5 |
| 319 | Hardness, elastic modulus, and structure of very hard carbon films produced by cathodicâ€•arc deposition with substrate pulse biasing. Applied Physics Letters, 1996, 68, 779-781. | 1.5 | 255 |
| 320 | Hollowâ€•anode plasma source for molecular beam epitaxy of gallium nitride. Review of Scientific Instruments, 1996, 67, 905-907. | 0.6 | 34 |
| 321 | Properties of cathodic arc deposited high-temperature superconducting composite thin films on Ag substrates. Physica C: Superconductivity and Its Applications, 1996, 270, 173-179. | 0.6 | 6 |
| 322 | High-resolution imaging of vacuum arc cathode spots. IEEE Transactions on Plasma Science, 1996, 24, 69-70. | 0.6 | 24 |
| 323 | Ion charge state distributions in high current vacuum arc plasmas in a magnetic field. IEEE Transactions on Plasma Science, 1996, 24, 1174-1183. | 0.6 | 162 |
| 324 | Plasma and Ion Beam Tools for Enhanced Battery Electrode Performance. Materials Research Society Symposia Proceedings, 1996, 438, 543. | 0.1 | 0 |

| # | Article | IF | Citations |
|---|---|---|---|
| 325 | Pressure-Controlled GaN MBE Growth Using a Hollow Anode Nitrogen Ion Source. Materials Research Society Symposia Proceedings, 1996, 449, 221. | 0.1 | 9 |
| 326 | Cathodic arc deposition of copper oxide thin films. Surface and Coatings Technology, 1996, 78, 168-172. | 2.2 | 19 |
| 327 | Surface modification of nickel battery electrodes by cobalt plasma immersion ion implantation and deposition. Surface and Coatings Technology, 1996, 85, 75-79. | 2.2 | 16 |
| 328 | Recent advances in vacuum arc ion sources. Surface and Coatings Technology, 1996, 84, 550-556. | 2.2 | 45 |
| 329 | Peristaltic ion source (invited). Review of Scientific Instruments, 1996, 67, 956-958. | 0.6 | 0 |
| 330 | Effect of pretreatment process parameters on diamond nucleation on unscratched silicon substrates coated with amorphous carbon films. Journal of Applied Physics, 1996, 79, 485-492. | 1.1 | 17 |
| 331 | High ion charge states in a highâ€current, shortâ€pulse, vacuum arc ion source. Review of Scientific Instruments, 1996, 67, 1202-1204. | 0.6 | 31 |
| 332 | In-situ deposition of sacrificial layers during ion implantation: concept and simulation. , 1996, , 1089-1092. | | 1 |
| 333 | Synthesis of unattainable ion implantation profiles â€“ â€˜Pseudo-implantation'. , 1996, , 646-650. | | 0 |
| 334 | Mechanical Properties of Amorphous Hard Carbon Films Prepared by Cathodic ARC Deposition. Materials Research Society Symposia Proceedings, 1995, 383, 453. | 0.1 | 20 |
| 335 | Film Synthesis on Powders by Cathodic ARC Plasma Deposition. Materials Research Society Symposia Proceedings, 1995, 388, 215. | 0.1 | 4 |
| 336 | New Developments in Metal Ion Implantation by Vacuum Arc Ion Sources and Metal Plasma Immersion. Materials Research Society Symposia Proceedings, 1995, 396, 467. | 0.1 | 2 |
| 337 | Formation of metal oxides by cathodic arc deposition. Surface and Coatings Technology, 1995, 76-77, 167-173. | 2.2 | 45 |
| 338 | Synthesis of unattainable ion implantation profiles â€” â€˜Pseudo-implantationâ€™. Nuclear Instruments & Methods in Physics Research B, 1995, 106, 646-650. | 0.6 | 10 |
| 339 | Increasing the retained dose by plasma immersion ion implantation and deposition. Nuclear Instruments & Methods in Physics Research B, 1995, 102, 132-135. | 0.6 | 21 |
| 340 | Preparation of cathodic arc deposited HTSC Bi/sub 2/Sr/sub 2/CaCu/sub 2/O/sub 8+y/-Ag composite thin films on Ag substrates. IEEE Transactions on Applied Superconductivity, 1995, 5, 2011-2014. | 1.1 | 4 |
| 341 | Nanoindentation and Nanoscratching of Hard Carbon Coatings for Magnetic Disks. Materials Research Society Symposia Proceedings, 1995, 383, 447. | 0.1 | 356 |
| 342 | The working principle of the hollow-anode plasma source. Plasma Sources Science and Technology, 1995, 4, 571-575. | 1.3 | 68 |

| # | Article | IF | Citations |
|---|---|---|---|
| 343 | Effect of intrinsic growth stress on the Raman spectra of vacuumâ€arcâ€deposited amorphous carbon films. Applied Physics Letters, 1995, 66, 3444-3446. | 1.5 | 102 |
| 344 | Transport of vacuum arc plasmas through magnetic macroparticle filters. Plasma Sources Science and Technology, 1995, 4, 1-12. | 1.3 | 173 |
| 345 | Development of hard carbon coatings for thin-film tape heads. IEEE Transactions on Magnetics, 1995, 31, 2976-2978. | 1.2 | 15 |
| 346 | Self-sustained self-sputtering: a possible mechanism for the superdense glow phase of a pseudospark. IEEE Transactions on Plasma Science, 1995, 23, 275-282. | 0.6 | 53 |
| 347 | Surface modification of magnetic recording heads by plasma immersion ion implantation and deposition. Journal of Applied Physics, 1994, 76, 1656-1664. | 1.1 | 20 |
| 348 | Metal ion implantation: Conventional versus immersion. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 823. | 1.6 | 35 |
| 349 | Effect of vacuum arc deposition parameters on the properties of amorphous carbon thin films. Surface and Coatings Technology, 1994, 68-69, 388-393. | 2.2 | 132 |
| 350 | Vacuum arc ion sources: Some vacuum arc basics and recent results (invited). Review of Scientific Instruments, 1994, 65, 1253-1258. | 0.6 | 21 |
| 351 | Effect of duct bias on transport of vacuum arc plasmas through curved magnetic filters. Journal of Applied Physics, 1994, 75, 4900-4905. | 1.1 | 96 |
| 352 | Vacuum-arc plasma deposition: macroparticle filtering, scaling, and other problems. , 1994, , . | | 1 |
| 353 | Electron emission from pseudospark cathodes. Journal of Applied Physics, 1994, 76, 1494-1502. | 1.1 | 43 |
| 354 | Vacuum arc ion source with filtered plasma for macroparticleâ€free implantation. Review of Scientific Instruments, 1994, 65, 1319-1321. | 0.6 | 15 |
| 355 | Focused injection of vacuum arc plasmas into curved magnetic filters. Journal of Applied Physics, 1994, 75, 4895-4899. | 1.1 | 54 |
| 356 | Metal plasma immersion ion implantation and deposition using vacuum arc plasma sources. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 815. | 1.6 | 151 |
| 357 | Vacuum arc deposition of multilayer X-ray mirrors. Surface and Coatings Technology, 1993, 61, 257-261. | 2.2 | 9 |
| 358 | Plasma synthesis of metallic and composite thin films with atomically mixed substrate bonding. Nuclear Instruments & Methods in Physics Research B, 1993, 80-81, 1281-1287. | 0.6 | 83 |
| 359 | On the macroparticle flux from vacuum arc cathode spots. IEEE Transactions on Plasma Science, 1993, 21, 440-446. | 0.6 | 103 |
| 360 | Time dependence of vacuum arc parameters. IEEE Transactions on Plasma Science, 1993, 21, 305-311. | 0.6 | 60 |

| # | Article | IF | Citations |
|---|---|---|---|
| 361 | Macroparticleâ€free thin films produced by an efficient vacuum arc deposition technique. Journal of Applied Physics, 1993, 74, 4239-4241. | 1.1 | 107 |
| 362 | Low Energy Ion Implantation / Deposition as a Film Synthesis and Bonding Tool. Materials Research Society Symposia Proceedings, 1993, 316, 833. | 0.1 | 12 |
| 363 | Model for explosive electron emission in a pseudospark â€˜â€˜superdense glowâ€™â€™. Physical Review Letters, 1993, 71, 364-367. | 2.9 | 48 |
| 364 | Joining of Metal Films to Carbon-Carbon Composite Material by Metal Plasma Immersion Ion Implantation. Materials Research Society Symposia Proceedings, 1993, 314, 205. | 0.1 | 5 |
| 365 | Vacuum arc cathode spot parameters from highâ€resolution luminosity measurements. Journal of Applied Physics, 1992, 71, 4763-4770. | 1.1 | 28 |
| 366 | Pressure ionization: its role in metal vapour vacuum arc plasmas and ion sources. Plasma Sources Science and Technology, 1992, 1, 263-270. | 1.3 | 38 |
| 367 | Brightness distribution and current density of vacuum arc cathode spots. Journal Physics D: Applied Physics, 1992, 25, 1591-1599. | 1.3 | 44 |
| 368 | Pulsed dye laser diagnostics of vacuum arc cathode spots. IEEE Transactions on Plasma Science, 1992, 20, 466-472. | 0.6 | 142 |
| 369 | Thermal instability of a super-high-pressure xenon discharge. IEEE Transactions on Plasma Science, 1991, 19, 324-328. | 0.6 | 3 |
| 370 | On modes of arc cathode operation. IEEE Transactions on Plasma Science, 1991, 19, 20-24. | 0.6 | 66 |
| 371 | Emission spectroscopy of low-current vacuum arcs. Journal Physics D: Applied Physics, 1991, 24, 1986-1992. | 1.3 | 56 |
| 372 | Electrode behaviour of pulsed high-pressure sodium lamps. Lighting Research & Technology, 1991, 23, 81-84. | 0.1 | 3 |
| 373 | Cathode mode transition in high-pressure discharge lamps at start-up. Lighting Research & Technology, 1990, 22, 111-115. | 0.1 | 15 |
| 374 | Effects of Nonâ€ideality and Nonâ€Equilibrium in the Cathode Spot Plasma of Vacuum Arcs. Contributions To Plasma Physics, 1989, 29, 537-543. | 0.5 | 23 |
| 375 | Validity conditions for complete and partial local thermodynamic equilibrium of nonhydrogenic level systems and their application to copper vapor arcs in vacuum. IEEE Transactions on Plasma Science, 1989, 17, 653-656. | 0.6 | 17 |
| 376 | Study of an Underexpanded Plasma Jet II. Diagnostics with Microwaves. Contributions To Plasma Physics, 1988, 28, 537-542. | 0.5 | 3 |
| 377 | Frozen state of ionisation in a cathodic plasma jet of a vacuum arc. Journal Physics D: Applied Physics, 1988, 21, 213-215. | 1.3 | 51 |
| 378 | Study of an Underexpanded Plasma Jet. Beitrage Aus Der Plasmaphysik, 1987, 27, 203-221. | 0.1 | 5 |

| # | Article | IF | Citations |
|---|---|---|---|
| 379 | Recombination of a Xenon Plasma Jet. Beitrage Aus Der Plasmaphysik, 1987, 27, 373-398. | 0.1 | 2 |
| 380 | A high-voltage surface effect on dielectrics in vacuum. Journal Physics D: Applied Physics, 1986, 19, L75-L77. | 1.3 | 1 |
| 381 | Lichtenberg Figures on Dielectrics in Gases and in Vacuum. Beitrage Aus Der Plasmaphysik, 1985, 25, 315-328. | 0.1 | 11 |
| 382 | Xiphophorus As An In Vivo Model for Studies on Normal and Defective Control of Oncogenes. Advances in Cancer Research, 1984, 42, 191-275. | 1.9 | 105 |
| 383 | Investigations on the mechanism of photodynamic action of different psoralens with DNA. Biophysics of Structure and Mechanism, 1983, 10, 11-30. | 1.9 | 12 |
| 384 | Microcalorimetric investigations of the metabolism of isolated human epidermis. Archives of Dermatological Research, 1979, 265, 173-180. | 1.1 | 5 |
| 385 | Models of DNA-dye-complexes: Energy transfer and molecular structures as evaluated by laser excitation. Applied Physics Berlin, 1979, 18, 333-338. | 1.4 | 22 |
| 386 | Genetics of susceptibility in the platyfish/swordtail tumor system to develop fibrosarcoma and rhabdomyosarcoma following treatment with N-methyl-N-nitrosourea (MNU). Zeitschrift FÃ¼r Krebsforschung Und Klinische Onkologie, 1978, 91, 301-315. | 0.8 | 24 |
| 387 | Genetic basis of susceptibility for development of neoplasms following treatment with N-methyl-N-nitrosourea (MNU) or X-rays in the platyfish/swordtail system. Experientia, 1978, 34, 780-782. | 1.2 | 51 |
| 388 | Etiology of cancer as studied in the platyfish-swordtail system. Biochimica Et Biophysica Acta: Reviews on Cancer, 1978, 516, 61-95. | 3.3 | 43 |
| 389 | Orthotopic and heterotopic autotransplantation of the rat kidney. Research in Experimental Medicine, 1978, 172, 123-129. | 0.7 | 0 |
| 390 | Energy transfer in nucleic acid-dye complexes. Optics Communications, 1978, 26, 339-342. | 1.0 | 16 |
| 391 | X ray-induced mutations of the genetically-determined melanoma system of xiphophorin fish. Experientia, 1971, 27, 931-932. | 1.2 | 14 |
| 392 | Effects of X-irradiation on the genetically-determined melanoma system of xiphophorin fish. Experientia, 1971, 27, 695-697. | 1.2 | 16 |
| 393 | XY females caused by X-irradiation. Experientia, 1969, 25, 871-871. | 1.2 | 5 |
| 394 | Focusing and neutralization of intense beams. , 0, , . | | 7 |
| 395 | Neutralized transport of high intensity beams. , 0, , . | | 5 |
| 396 | Ion formation in vacuum arc cathode spots. , 0, , . | | 0 |

| # | Article | IF | Citations |
|---|---|---|---|
| 397 | Surface resistivity tailoring of ceramic accelerator components. , 0, , . | | 2 |
| 398 | Copper Oxide Films Formed By Reactive Cathodic Arc Deposition. , 0, , . | | 0 |
| 399 | High Charge State Metal Ion Production In Vacuum Arc Ion Sources. , 0, , . | | 0 |
| 400 | Influence of a strong pulsed magnetic field on the charge state distribution of ions in a vacuum arc plasma. , 0, , . | | 3 |
| 401 | Predicting ion charge state distributions of vacuum arc plasmas. , 0, , . | | 2 |
| 402 | Vacuum-arc-generated macro particles in the nanometer range. , 0, , . | | 2 |
| 403 | Plasma fluctuations, local partial Saha equilibrium, and the broadening of vacuum-arc ion charge state distributions. , 0, , . | | 1 |
| 404 | Results from ZMEVVA: A new source for heavy-ion accelerators. , 0, , . | | 1 |
| 405 | Recent study of ion charge state distribution in vacuum arc ion sources. , 0, , . | | 1 |
| 406 | Increasing the ion charge states in vacuum arc plasmas by arc current spikes. , 0, , . | | 1 |
| 407 | A periodic table of ion charge state distributions observed in the transition region between vacuum sparks and vacuum arcs. , 0, , . | | 1 |
| 408 | Ultrathin diamondlike carbon films deposited by filtered carbon vacuum arcs. , 0, , . | | 0 |
| 409 | The sheath around biased objects immersed in streaming vacuum arc plasmas. , 0, , . | | 0 |
| 410 | Enhancement of high-charge-state ions in vacuum arc ion sources. , 0, , . | | 0 |
| 411 | Compact vacuum arc thruster for small satellite systems. , 0, , . | | 3 |
| 412 | Magnetic field effect on the sheath in plasma immersion ion implantation. , 0, , . | | 0 |
| 413 | Effect of self-bias on transport of vacuum arc plasmas through magnetic filters. , 0, , . | | 0 |
| 414 | Cathodic are spots: Ignition probability as a a fundamental concept to describe spot types, phases, and motion. , 0, , . | | 1 |

| # | Article | IF | Citations |
|---|---|---|---|
| 415 | Measurement of total ion flux in vacuum are discharges. , 0, , . | | 3 |